

IN THE SPECIFICATION:

Please replace the paragraph beginning on page 5, line 18, beginning "In this case the determined thickness...", with the following rewritten paragraph:

A1  
--In this case the determined thickness means the thickness of the surface layer of silicon necessary to obtain a given optical behavior. For example, it may be a thickness equal to or proportional to  $\left[ \frac{\ddot{e}}{4n_s} \right] \frac{\lambda}{4n_s}$  where  $\lambda$  is the working wavelength of produced or received light and  $n_s$  is the refraction index of silicon.--

Please replace the paragraph beginning on page 11, line 19, beginning "It is observed that after cleavage...", with the following rewritten paragraph:

A2  
--It is observed that after cleavage has terminated, the surface layer 22a remains fixed to the platform 10 through the silicon oxide layer 12a.--

Please replace the paragraph beginning on page 11, line 27, beginning "Figure 4 shows the assembly consisting of the platform...", with the following rewritten paragraph:

A3  
--Figure 4 shows the assembly consisting of the platform 10, the oxide layer 12a and the surface layer 22a. The assembly is inverted compared with the assembly in Figure 3. An arrow 24 indicates the treatment applied to adjust the thickness of the surface layer.--

Please replace the paragraph beginning on page 12, line 3, beginning "In the example described, the initial thickness...", with the following rewritten paragraph:

A4  
--In the example described, the initial thickness of the surface layer 22a is greater than the required thickness. Thus, the thickness adjustment treatment consists of thinning the layer. This treatment may be made by polishing or by a series of surface oxidation and